



(11) **EP 1 739 484 A8**

(12) **CORRECTED EUROPEAN PATENT APPLICATION**

Note: Bibliography reflects the latest situation

(15) Correction information:

Corrected version no 1 (W1 A2)
INID code(s) 62

(51) Int Cl.:

G03F 7/029 (2006.01)

(48) Corrigendum issued on:

09.05.2007 Bulletin 2007/19

(43) Date of publication:

03.01.2007 Bulletin 2007/01

(21) Application number: **06121351.8**

(22) Date of filing: **18.04.2001**

(84) Designated Contracting States:
DE

(30) Priority: **19.04.2000 JP 2000117803**
01.05.2000 JP 2000131995
01.05.2000 JP 2000131996
30.11.2000 JP 2000364310
04.12.2000 JP 2000368412
05.12.2000 JP 2000369415
25.01.2001 JP 2001016537

(62) Document number(s) of the earlier application(s) in accordance with Art. 76 EPC:
01109621.1 / 1 148 387

(71) Applicant: **LASTRA S.P.A.**
I-25025 Manerbio (IT)

(72) Inventors:

- **Urano, Toshiyuki**
Kanagawa (JP)
- **Kohori, Kazuhiro**
Kanagawa (JP)
- **Okamoto, Hideaki**
Kanagawa (JP)

(74) Representative: **Goedeweck, Rudi**
AGFA-GEVAERT
Corporate IP Department 3800,
Patent Administration,
Septestraat 27
2640 Mortsel (BE)

Remarks:

This application was filed on 27 - 09 - 2006 as a divisional application to the application mentioned under INID code 62.

(54) **Photosensitive lithographic printing plate and method for making a printing plate.**

(57) A photosensitive lithographic printing plate comprises a photosensitive layer and a protective layer formed in this order on a support, wherein the photosensitive layer has a maximum peak of spectral sensitivity within a wavelength range ranging from 390 to 430 nm, the minimum exposure for the photosensitive lithographic printing plate for image formation at a wavelength of

410 nm (S410) is at most 100 $\mu\text{J}/\text{cm}^2$, and the relation between the minimum exposure for image formation at a wavelength of 450 nm (S450) and the minimum exposure for image formation at a wavelength of 410 nm (S410) is $0 < S410/S450 \leq 0.1$.

EP 1 739 484 A8